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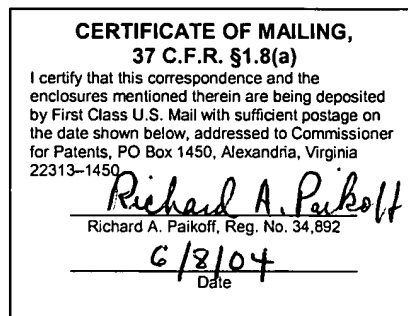
**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application No. : 10/040,042 Confirmation No. 1835  
Applicant : Wei-Yu Su  
Filed : November 7, 2001  
TC/A.U. : 1746  
Title : Method for Reduction of Photomask Defects

Docket No. : N1085-90003  
Customer No. : 08933

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450



**AMENDMENT AND RESPONSE**

Sir:

In response to the Office Action of March 9, 2004, please amend the above-identified application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 4 of this paper.

**Amendments to the Drawings** begin on page 8 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

**Remarks** begin on page 9 of this paper.